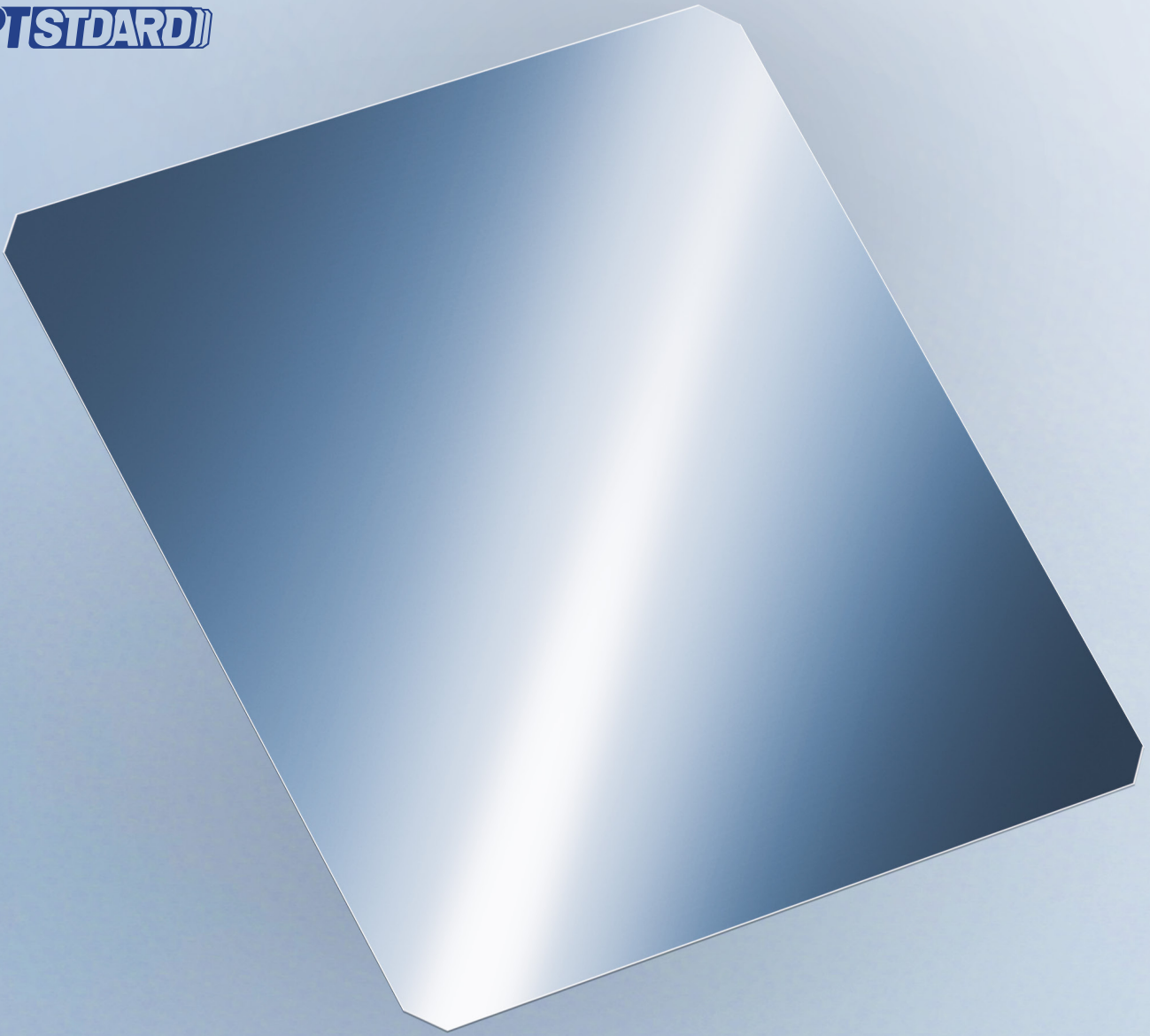


**PTSTANDARD**



# Mono Silicon Wafer

Data Sheet

**P-Type** 182.2\*183.75±0.25mm

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# Mono Silicon Wafer

## Data Sheet

**P-Type** 182.2\*183.75±0.25mm

### Material Performance Parameters

|   |                 |  |
|---|-----------------|--|
| Conductivity Type                       | P               | P/N type tester                              |
| Doped element                           | Gallium         | /  |
| Crystallinity                           | Single crystal  | Priority etching technology (FSTM F47-88)    |
| Dislocation density/pcs/cm <sup>2</sup> | ≤500            | Priority etching technology (FSTM F47-88)    |
| Surface orientation                     | <100>±3°        | X-ray diffractometer                         |
| Lateral crystal orientation             | <010>, <001>±3° | X-ray diffractometer                         |
| Oxygen content (ppma)                   | ≤16             | FTIR (ASTM F121-83)                          |
| Carbon content (ppma)                   | ≤1              | FTIR (ASTM F123-91)                          |
| Lifetime (μs)                           | ≥70             | BCT-400                                      |
| Resistivity (Ω.cm)                      | 0.4-1.1         | Silicon wafer automatic inspection equipment |

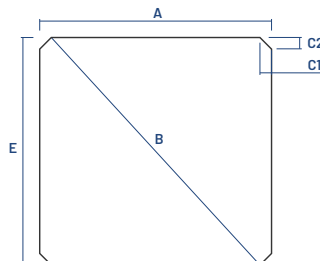
### Geometric Rule Parameters

|                              |                        |  |
|------------------------------|------------------------|--|
| Chamfered edge shape         | Round                  | /  |
| Wafer margins (mm)           | Short edge: 182.2±0.25 | Silicon wafer automatic inspection equipment |
|                              | Long edge: 183.75±0.25 | Silicon wafer automatic inspection equipment |
| Wafer diameter (mm)          | φ247±0.25mm            | Silicon wafer automatic inspection equipment |
| Arc length projection (mm)   | 8.57/8.49 ±0.5mm       | Silicon wafer automatic inspection equipment |
| Perpendicularity             | 90±0.15°               | Silicon wafer automatic inspection equipment |
| Thickness specification (μm) | 130/135±10             | Silicon wafer automatic inspection equipment |

### Appearance Quality

|                          |                                      |  |
|--------------------------|--------------------------------------|--|
| Surface quality          | No visible pollution                 | Silicon wafer automatic inspection equipment |
|                          | No color difference, No bright lines |  |
| Edge Chipping            | Depth≤0.3mm , Length ≤0.5mm          | Silicon wafer automatic inspection equipment |
|                          | Count ≤ 2/pcs, no V-shaped           |  |
| Saw mark (μm)            | ≤15                                  | Silicon wafer automatic inspection equipment |
| Warp/bending degree (μm) | ≤40                                  | Silicon wafer automatic inspection equipment |
| TTV (μm)                 | ≤25                                  | Silicon wafer automatic inspection equipment |
| Micro-crack/void         | None                                 | Silicon wafer automatic inspection equipment |

Wafer dimensions



Size: 182.2\*183.75±0.25mm

A: 182.2±0.25mm

E: 183.75±0.25mm

B: φ 247±0.25mm

C1: 8.57±0.5mm

C2: 8.49±0.5mm